L Number	Hits	Search Text	DB	Time stamp
1	62271	(etch$3 clean$3) and (wafer substrate) and (bath container tank)	USPAT; US-PGPUB	2003/07/05 15:37
2	3382	((etch$3 clean$3) and (wafer substrate) and (bath container tank)) and ((etch$3 clean$3) near10 (wafer substrate) near10 (bath container tank))	USPAT; US-PGPUB	2003/07/05 15:38
4	2842	(((etch$3 clean$3) and (wafer substrate) and (bath container tank)) and ((etch$3 clean$3) near10 (wafer substrate) near10 (bath container tank))) and (liquid solution)	USPAT; US-PGPUB	2003/07/05 15:38
5	830	((((etch$3 clean$3) and (wafer substrate) and (bath container tank)) and ((etch$3 clean$3) near10 (wafer substrate) near10 (bath container tank))) and (liquid solution)) and ("HF" (hydrogn near fluoride) (hydro near3 fluoric near3 acid))	USPAT; US-PGPUB	2003/07/05 15:38
6	7119	(etch$3 clean$3) and (wafer substrate) and (bath container tank)	EPO; JPO; DERWENT; IBM_TDB	2003/07/05 15:38
7	2798	((etch$3 clean$3) and (wafer substrate) and (bath container tank)) and ((etch$3 clean$3) near10 (wafer substrate) near10 (bath container tank))	EPO; JPO; DERWENT; IBM_TDB	2003/07/05 15:38
8	1722	(((etch$3 clean$3) and (wafer substrate) and (bath container tank)) and ((etch$3 clean$3) near10 (wafer substrate) near10 (bath container tank))) and (liquid solution)	EPO; JPO; DERWENT; IBM_TDB	2003/07/05 15:38
9	50	((((etch$3 clean$3) and (wafer substrate) and (bath container tank)) and ((etch$3 clean$3) near10 (wafer substrate) near10 (bath container tank))) and (liquid solution)) and ("HF" (hydrogn near fluoride) (hydro near3 fluoric near3 acid))	EPO; JPO; DERWENT; IBM_TDB	2003/07/05 15:39